

U.S. Department of Commerce, Patent and Trademark Office

Atty Docket No.

Serial No.

M-11912 US

10/033,114

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Applicants

Tai-Peng Lee et al.

Filing Date

Group

October 22, 2001

Not assigned yet

U.S. Patent Documents

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
AA						
AB						
AC						
AD						
AE						
AF						
AG						
AH						
AI						
AJ						
AK						

Foreign Patent Documents

Document	Date	Country	Class	Subclass	Translation
AL					Yes No
AM					
AN					
AO					
AP					

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

JAG	AQ	S.V. Nguyen, "High Density Plasma Chemical Vapor Deposition of Silicon-based Dielectric Films For Integrated Circuits" (visited 26 July 2001) < http://www.research.ibm.com/journal/rd/431/nguyen.html >.
	AR	
	AS	

Examiner *James A. Hurd*

Date Considered *June 7, 2003*

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.